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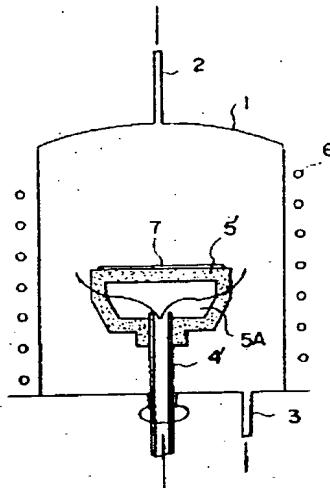
(54) MANUFACTURING EQUIPMENT OF
SEMICONDUCTOR

(57) Abstract:

PURPOSE: To enable discharging impurity rapidly and easily by providing a hollow susceptor made of porous carbon.

CONSTITUTION: A manufacturing equipment of semiconductor consists of a reaction chamber 1, an air pipe 2, an exhaust pipe 3, a tube 4', a susceptor 5' and a high frequency heating coil 6. The susceptor 5' is heated by a high frequency radio wave and the heat is conducted to a substrate 7 for heating. The susceptor 5' is made of porous carbon and the inside 5A is hollow. This construction enables discharging a reaction gas rapidly and easily since the susceptor 5' is made of porous carbon even if the reaction gas is absorbed by the susceptor 5'.

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Porous Hollow Loft
Not Sealed on
Wires